## LISTING OF THE CLAIMS

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A system for reducing oxidation of a semiconductor device, comprising:

a holding device for securing <u>a lead frame for</u> the semiconductor device to a platform, the holding device including an opening providing access by a bonding tool to an area where the semiconductor device is to be heated;

the holding device further including a cover, the cover defining a hollow cavity located adjacent to the opening;

a gas inlet in fluid communication with the cavity and the opening for supplying a relatively inert gas; and

the holding device further defining a conduit connecting the gas inlet and hollow cavity, the conduit having a smaller cross-sectional area than the cavity, the conduit for transmitting the inert gas to the opening through the cavity.

2. (Previously Presented) A system a claimed in claim 1, wherein the cavity is configured such that the inert gas supplied to the cavity is directed away from an outlet connecting the cavity to the opening.

## 3. - 5. (Canceled)

6. (Previously Presented) A system as claimed in claim 1, wherein the gas inlet is formed in the holding device.

- 7. (Previously Presented) A system as claimed in claim 1, wherein the gas inlet is formed in the platform.
- 8. (Previously Presented) A system as claimed in claim 1, wherein a space is defined between the holding device and the platform for receiving the inert gas from the gas inlet and for distributing the inert gas over a surface of the electronic device.
- 9. (Previously Presented) A system as claimed in claim 8, wherein the space is connected to the said opening for distributing an amount of the inert gas directly from the space to the opening.
- 10. (Previously Presented) A system as claimed in claim 8, wherein the conduit links the cavity and the space and channels an amount of the inert gas from the space to the cavity.
- 11. 16. (Canceled)